

Amendment and Response Under 37 C.F.R. §1.116 - Expedited Examining Procedure

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Serial No.: 09/651,702

Confirmation No.: 2471

Filed: August 30, 2000

For: SUPERCRITICAL COMPOSITIONS FOR REMOVAL OF ORGANIC MATERIAL AND METHODS OF USING SAME

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**Amendments to the Claims**

This listing of claims replaces all prior versions, and listings, of claims in the above-identified application:

1-19. (Canceled)

20. (Currently Amended) A The composition of claim 19 comprising sulfur trioxide (SO<sub>3</sub>) in a supercritical state, wherein the composition further comprises at least one oxidizer selected from the group consisting of sulfur dioxide (SO<sub>2</sub>), nitrous oxide (N<sub>2</sub>O), NO, NO<sub>2</sub>, ozone (O<sub>3</sub>), hydrogen peroxide (H<sub>2</sub>O<sub>2</sub>), F<sub>2</sub>, Cl<sub>2</sub>, Br<sub>2</sub>, and oxygen (O<sub>2</sub>), and wherein the composition is an organic material removal composition.

21. (Previously Presented) The composition of claim 20, wherein the at least one oxidizer is in a supercritical state.

22-24. (Canceled)

25. (Previously Presented) A composition comprising sulfur trioxide (SO<sub>3</sub>) in a supercritical state and an oxidizer, wherein the composition is an organic material removal composition.

26. (Canceled)

27. (Previously Presented) A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO<sub>2</sub>), ammonia (NH<sub>3</sub>), H<sub>2</sub>O, nitrous oxide (N<sub>2</sub>O), carbon monoxide (CO), nitrogen (N<sub>2</sub>), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

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a second component selected from the group consisting of sulfur dioxide (SO<sub>2</sub>), nitrous oxide (N<sub>2</sub>O), NO, NO<sub>2</sub>, ozone (O<sub>3</sub>), hydrogen peroxide (H<sub>2</sub>O<sub>2</sub>), F<sub>2</sub>, Cl<sub>2</sub>, Br<sub>2</sub>, and oxygen (O<sub>2</sub>); and sulfur trioxide (SO<sub>3</sub>) in a supercritical state, wherein the composition is an organic material removal composition.

28. (Previously Presented) The composition of claim 27, wherein the first component is carbon dioxide.

29. (Previously Presented) The composition of claim 27, wherein a ratio of the first component to the total of the second component plus sulfur trioxide is about 1:100 by volume to about 100:1 by volume.

30. (Canceled)

31. (Previously Presented) The composition of claim 28, wherein a ratio of carbon dioxide:sulfur trioxide is about 10:1 by volume to about 1:1 by volume.

32. (Previously Presented) The composition of claim 27, wherein the first component is in a supercritical state.

33-42. (Canceled)

43. (Previously Presented) The composition of claim 27, wherein the second component is in a supercritical state.

44. (Previously Presented) The composition of claim 27, wherein the first component and the second component are both in supercritical states.

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45. (Canceled)

46. (Currently Amended) The composition of claim ~~20~~ 19 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.

47. (Previously Presented) The composition of claim 25 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.

48. (Previously Presented) The composition of claim 27 further comprising a component selected from the group consisting of hydrogen chloride, hydrogen bromide, hydrogen fluoride, ammonium fluoride, tetramethylammonium fluoride, tetramethylammonium hydroxide, beta-diketones, fluorinated-diketones, organic acids, and combinations thereof.

49. (Canceled)

50. (Previously Presented) A composition comprising sulfur trioxide (SO<sub>3</sub>) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from an object.

51. (Previously Presented) A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO<sub>2</sub>), ammonia (NH<sub>3</sub>), H<sub>2</sub>O, nitrous oxide (N<sub>2</sub>O), carbon monoxide (CO), nitrogen (N<sub>2</sub>), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

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a second component selected from the group consisting of sulfur dioxide (SO<sub>2</sub>), nitrous oxide (N<sub>2</sub>O), NO, NO<sub>2</sub>, ozone (O<sub>3</sub>), hydrogen peroxide (H<sub>2</sub>O<sub>2</sub>), F<sub>2</sub>, Cl<sub>2</sub>, Br<sub>2</sub>, and oxygen (O<sub>2</sub>); and sulfur trioxide (SO<sub>3</sub>) in a supercritical state, wherein the composition is a composition for removing exposed organic material from an object.

52. (Canceled)

53. (Previously Presented) A composition comprising sulfur trioxide (SO<sub>3</sub>) in a supercritical state and an oxidizer, wherein the composition is a composition for removing exposed organic material from a substrate assembly.

54. (Previously Presented) A composition comprising:

a first component selected from the group consisting of carbon dioxide (CO<sub>2</sub>), ammonia (NH<sub>3</sub>), H<sub>2</sub>O, nitrous oxide (N<sub>2</sub>O), carbon monoxide (CO), nitrogen (N<sub>2</sub>), helium (He), neon (Ne), argon (Ar), krypton (Kr), and xenon (Xe);

a second component selected from the group consisting of sulfur dioxide (SO<sub>2</sub>), nitrous oxide (N<sub>2</sub>O), NO, NO<sub>2</sub>, ozone (O<sub>3</sub>), hydrogen peroxide (H<sub>2</sub>O<sub>2</sub>), F<sub>2</sub>, Cl<sub>2</sub>, Br<sub>2</sub>, and oxygen (O<sub>2</sub>); and sulfur trioxide (SO<sub>3</sub>) in a supercritical state, wherein the composition is a composition for removing exposed organic material from a substrate assembly.

55. (New) The composition of claim 20 further comprising a substrate assembly in contact with the organic material removal composition.

56. (New) The composition of claim 25 further comprising a substrate assembly in contact with the organic material removal composition.

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57. (New) The composition of claim 27 further comprising a substrate assembly in contact with the organic material removal composition.

58. (New) The composition of claim 50 further comprising a substrate assembly in contact with the composition for removing exposed organic material from an object.

59. (New) The composition of claim 51 further comprising a substrate assembly in contact with the composition for removing exposed organic material from an object.